PTC/SB/06A(10-01)
Approved for use through 10/31/2002, OMB 651-0031
Patent & Trademark Office: U.S. DEPARTMENT OF COMMERCE

	Under the Paperwork Reduction Act of 1995, no persons are	required to respond to a collection of information unless it contains a valid OMB control number		
Substitute for form 1449A/PTO INFORMATION DISCLOSURE	Complete if Known			
STATEMENT BY APPLICANT (Use as many sheets as necessary)	Application Number	Unknown 10/789-028		
	Filing Date	Even Date Herewith 02-27-04		
	First Named Inventor	Forbes, Leonard		
	Group Art Unit	Unknown 2827		
	Examiner Name	Pham, Ly		
Sheet 1 of 5	Attorney Docket No: 1	1303.024US2		

US PATENT DOCUMENTS						
Examiner Initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate
LP.	US- 2001/0013621	08/16/2001	Nakazato, Kazuo	257	314	12/08/2000
	US- 2002/0106536	08/08/2002	Lee, Jongho, et al.	428	702	02/02/2001
	US- 2002/0137250	09/26/2002	Nguyen, B., et al.	438	53	03/15/2002
	US-4,295,150	10/13/1981	Adam, Fritz	357	54	10/01/1979
	US-4,412,902	11/01/1983	Michikami, Osamu, et al.	204	192	06/18/1982
	US-4,757,360	07/12/1988	Faraone, Lorenzo, et al.	357	23.5	07/06/1983
	US-4,780,424	10/25/1988	Holler, Mark A.	437	29	09/28/1987
	US-5,042,011	08/20/1991	Casper, Stephen L., et al.	365	205	05/22/1989
	US-5,071,782	12/10/1991	Mori, Kiyoshi	437	48	06/28/1990
	US-5,073,519	12/01/1991	Rodder, Mark .	438	269	10/31/1990
	US-5,280,205	06/18/1994	Green, Robert S., et al.	307	530	04/16/1992
	US-5,350,738	09/27/1994	Hase, Takashi, et al.	505	473	11/27/1992
	US-5,399,516	03/21/1995	Bergendahl, A., et al.	437	43	09/21/1992
	US-5,418,389	05/23/1995	Watanabe, Y.	257	295	11/09/1993
	US-5,497,494	03/05/1996	Combs, J., et al.	395	750	07/23/1993
	US-5,498,558	03/12/1996	Kapoor, A	437	43	05/06/1994
	US-5,508,544	04/16/1996	Shah, P. L.	257	316	09/27/1994
	US-5,600,592	02/04/1997	Atsumi, S., et al.	365	185.18	05/08/1995
	US-5,618,575	04/08/1997	Peter, Gunter	427	8	04/21/1995
	US-5,627,785	05/06/1997	Gilliam, Gary R., et al.	365	189.01	03/15/1996
	US-5,677,867	10/14/1997	Hazani, E.	365	185	06/30/1995
	US-5,691,230	11/25/1997	Forbes, Leonard	437	62	09/04/1996
	US-5,801,401	09/01/1998	Forbes, Leonard	257	77	01/29/1997
	US-5,852,306	12/22/1998	Forbes, Leonard	257	315	01/29/1997
	US-5,880,991	03/09/1999	Hsu, L., et al.	365	182	04/14/1997
	US-5,923,056	07/13/1999	Lee, Woo-Hyeong, et al.	257	192	03/12/1998
	US-5,936,274	08/10/1999	Forbes, Leonard, et al.	257	315	07/08/1997
1	US-5,981,350	11/09/1999	Geusic, Joseph E., et al.	438	386	05/29/1998
	US-5,986,932	11/16/1999	Ratnakumar, K. N., et al.	365	185.07	06/30/1997
	US-5,991,225	11/23/1999	Forbes, Leonard, et al.	365	230.06	02/27/1998
	US-6,025,228	02/15/2000	Ibok, E., et al.	438	261	11/25/1997
	US-6,025,627	02/15/2000	Forbes, Leonard, et al.	257	321	05/29/1998
	US-6,031,263	02/29/2000	Forbes, Leonard, et al.	257	315	07/29/1997
1.	US-6,069,380	05/30/2000	Chou, S. Y., et al.	257	315	07/25/1997
	US-6,069,816	05/30/2000	Nishimura, Kiyoshi	365	145	11/24/1998
	US-6,124,729	09/26/2000	Noble, Wendell P., et al.	326	41	02/27/1998
V	US-6,134,175	10/17/2000	Forbes, Leonard, et al.	365	230.06	08/04/1998

EXAMINER Pham hu DATE CONSIDERED 66/28/05

PTC/S8/084(10.01)
Approved for use through 10/31/2002, OMB 851-0031
US Pases & Trademan Office U.B. DEPARTMENT OF COMMERCE
clion of Information unitses is Contained and the Contained of the Con

Substitute for form 1449A/PTO	Under the Paperwork Raduction Act of 1995, no pursons are required to respond to a collection of information unless it contains a valid CNRS control number. Complete if Known				
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	Unknown 10/789, 038			
(Use as many sheets as necessary)	Filing Date	Even Date Herewith 02-27-04			
	First Named Inventor	Forbes, Leonard			
	Group Art Unit	Unknown 2827			
	Examiner Name	Pham, Ly			
Sheet 2 of 5	Attorney Docket No: 1	1303.024US2			

	US-6,135,175	10/24/2000	Gaudreault, P., et al.	144	4.1	10/19/1998
1	US-6,141,238	10/31/2000	Forbes, L., et al.	365	145	08/30/1999
	US-6,141,248	10/31/2000	Forbes, L., et al.	365	185.08	07/29/1999
	US-6,143,636	11/07/2000	Forbes, Leonard, et al.	438	587	08/20/1998
	US-6,153,468	11/28/2000	Forbes, Leonard, et al.	438	257	05/17/1999
	US-6,163,049	12/19/2000	Bui, N. D.	257	321	10/13/1998
	US-6,208,164	03/27/2001	Noble, Wendell P., et al.	326	41	08/04/1998
	US-6,210,999	04/03/2001	Gardner, Mark I., et al.	438	183	12/04/1998
	US-6,229,175	05/08/2001	Uchida, Hidetsugu	257	315	03/19/1999
	US-6,238,976	05/29/2001	Noble, Wendell P., et al.	438	259	02/27/1998
	US-6,246,606	06/12/2001	Forbes, Leonard, et al.	365	185.03	09/02/1999
	US-6,249,020	06/19/2001	Forbes, Leonard, et al.	257	315	08/27/1998
	US-6,249,460	06/19/2001	Forbes, Leonard, et al.	365	185.28	02/28/2000
	US-6,307,775	10/23/2001	Forbes, Leonard, et al.	365	185.01	08/27/1998
	US-6,323,844	11/27/2001	Yeh, Fu-Kuo, et al.	345	166	08/11/1997
	US-6,351,411	02/26/2002	Forbes, Leonard, et al.	365	182	06/12/2001
	US-6,424,001	07/23/2002	Forbes, Leonard, et al.	257	315	02/09/2001
	US-6,461,931	10/08/2002	Eldridge, Jerome M.	438	398	08/29/2000
	US-6,541,280	04/01/2003	Kaushik, Vidya S., et al.	438	3	03/20/2001
V	US-6,586,797	07/01/2003	Forbes, Leonard, et al.	257	325	08/30/2001

FOREIGN PATENT DOCUMENTS					
Examiner Foreign Document No Initials*	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	T ²

	ОТНІ	ER DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
LP.		AARIK, JAAN, et al., "Anomalous effect of temperature on atomic layer deposition of titanium oxide", Journal of Crystal Growth, (2000),pp. 531-537	
		AARIK, JAAN, et al., "Texture development in nanocrystalline hafnium dioxide thin films grown by atomic layer deposition", <u>Journal of Crystal Growth, 220(1-2)</u> , (2000),105-113	
		AFANAS'EV, V, et al., "Electron energy barriers between (100)Si and ultrathin stacks of SiO2, Al2O3, and ZrO3 and ZrO2 insulators", Applied Physics Letters, 78(20), (2001),pp. 3073-3075	
		ARYA, S., et al., "Conduction Properties of Thin Al2O3 Films", Thin Solid Films, 91, (1982),363-374	
		DIPERT, BRIAN, "Flash Memory Goes Mainstream", <u>IEEE Spectrum, 30(10)</u> , (October 1993),48-52	
V		EIERDAL, L., et al., "Interaction of oxygen with Ni(110) studied by scanning tunneling microscopy", Surface Science, 312, (1994),pp. 31-53	

EXAMINER ALAM MIN MIN DATE CONSIDERED 06/28/05

PTC/SB/08A(10-01)
Approved for use through 10/31/2002. OMB 651-0031
US Patent & Trademic Office: US. DEPARTMENT OF COMMERCE
on of information unfease is confusing a visial GMB control number.

Substitute for form 1449A/PTO	Under the Peperwork Reduction Act of 1960, no persons are required to respond to a conscious of resumation unless it consists a valid UNIX contact number. Complete if Known				
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)	Application Number	Unknown 10/784.038			
	Filing Date	Even Date Herewith 02-27-04			
	First Named Inventor	Forbes, Leonard			
	Group Art Unit	Unknown 2827			
	Examiner Name Pham, Ly				
Sheet 3 of 5	Attorney Docket No:	1303.024US2			

	ОТН	ER DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Ť²
LP		ELDRIDGE, J., et al., "Analysis of Ultrathin Oxide Growth on Indium", Thin Solid Films, 12, (1972),pp. 447-451	
<u>V</u>		ELDRIDGE, J., et al., "Measurement of Tunnel Current Density in a Metal-Oxide-	
		Metal System as a Function of Oxide Thickness", Proc. 12th Intern. Conf. on Low	
		Temperature Physics, (1971),427-428	
		ELDRIDGE, J.M., et al., "The Growth of Thin PbO Layers on Lead Films", Surface	
	ļ	Science Vol. 40, (1973),512-530	
		FERGUSON, J D., et al., "Atomic layer deposition of Al2O3 and SiO2 on BN particles using sequential surface reaction", Applied Surface Science, (2000),pp.	
1		280-292	<u> </u>
		GREINER, J., "Josephson Tunneling Barriers by rf Sputter Etching in an Oxygen Plasma", Journal of Applied Physics, 42(12), (November 1971),5151-5155	
		GREINER, J., "Oxidation of lead films by rf sputter etching in an oxygen plasma", Journal of Applied Physics, 45(1), (1974),32-37	
 		GRIMBOLT, J., "I. Interaction of Al Films with O2 at Low Pressures", <u>Journal of</u>	
		the Electrochemical Society, 129(10), (1982),pp. 2366-2368	
		GRIMBOLT, J., "II. Oxidation of Al Films", Journal of Electrochem Soc.: Solid-	
		State Science and Technology, (1982),pp. 2369-2372	ļ
		GUNDLACH, K., et al., "Logarithmic Conductivity of Al-Al2O3-Al Tunneling	
		Junctions Produced by Plasma and by Thermal Oxidation", Surface Science, 27, (1971),125-141	
	ļ 	GUO, X., "High Quality Ultra-thin (1.5 nm) TiO2/Si3N4 Gate Dielectric for Deep	
		Sub-micron CMOS Technology", IEDM Technical Digest, (1999),pp. 137-140	
		HODGES, D. A., Analysis and Design of Digital Integrated Circuits, 2nd Edition,	
ļ ļ		McGraw-Hill Publishing. New York,(1988),pp. 354-357, 394-396 HURYCH, Z., "Influence of Non-Uniform Thickness of Dielectric Layers on	-
		Capacitance and Tunnel Currents", Solid-State Electronics, vol. 9, (1966),967-979	
 		ITOKAWA, H, "Determination of Bandgap and Energy Band Alignment for High-	
		Dielectric-Constant Gate Insulators Using High-Resolution X-ray Photoelectron	
		Spectroscopy", Extended Abstracts of the 1999 International Conference on Solid	
		State Devices and Materials, (1999),pp. 158-159	ļ
		KIM, YONG S., et al., "Effect of rapid thermal annealing on the structure and the	1
		electrical properties of atomic-layer-deposited Ta2O5 films", <u>Journal of the Korean</u>	
	 	Physical Society, (December 2000),pp. 975-979 KIM, H., "Leakage current and electrical breakdown in metal-organic chemical	
		vapor deposited TiO2 dielectrics on silicon substrates", Applied Phys. Lett., 69(25).	
		(1996),pp. 3860-3862	
 	 	KIM, YEONG K., et al., "Novel capacitor technology for high density stand-alone	
	1	and embedded DRAMs", <u>IEDM</u> , (2000),pp. 369-372	
V		KUBASCHEWSKI, O., et al., Oxidation of Metals and Alloys, Second Edition,	
	<u></u>	Butterworths, London (1962), pp. 1-3, 5,6, 8-12, 24, 36-39, 53-63	<u>i </u>

EXAMINER alaman	M	DATE CONSIDERED	06/28/05	_

PTC/SB/06A(10-01)
Acproved for use liveuigh 10/31/2002, OMB 851-0001
US Patent & Trademark Office U.S. DEPARTMENT OF COMMERCE

Substitute for form 1449A/PTO	Complete if Known				
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)	Application Number	Unknown 10/789,038			
	Filing Date	Even Date Herewith 02-27-04			
	First Named Inventor	Forbes, Leonard			
	Group Art Unit	Unknown 2827			
	Examiner Name	Pham, Ly			
Sheet 4 of 5	Attorney Docket No:	1303.024US2			

	OTH	ER DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No 1	include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	İ
10		KUKLI, KAUPO, "Atomic Layer Deposition of Titanium Oxide from Til4 and	
H		H2O2", Chemical Vapor Deposition, 6(6), (2000),303-310	L
,		KUKLI, KAUPO, et al., "Atomic layer deposition of zirconium oxide from zirconium	
}		tetraiodide, water and hydrogen peroxide", <u>Journal of Crystal Growth</u> , (2001),pp. 262-272	
		KUKLI, K., "Development of Dielectric Properties of Niobium Oxide, Tantalum	
		Oxide, and Aluminum Oxide Based Nanolayered Materials", Journal of the	
1		Electrochemical Society, 148(2), (2001),pp. F35-F41	
		KUKLI, KAUPO, et al., "Real-time monitoring in atomic layer deposition of TiO2	
		from Til4and H2O-H2O2", American Chemical Society, (2000),pp. 8122-8128	
		KWO, J., "Properties of high k gate dielectrics Gd2O3 and Y2O3 for Si", Journal	
1 1		of Applied Physics, 89(7), (2001),pp. 3920-3927	
	<u> </u>	LEE, J., et al., "Effect of Polysilicon Gate on the Flatband Voltage Shift and	
		Mobility Degradation for ALD-Al2O3 Gate Dielectric", IEDM, (2000),pp. 645-648	
		LUAN, H. F., "High Quality Ta2O5 Gate Dielectrics with Tox,eq<10A", IEDM	
		Technical Digest, International Electron Devices Meeting, (December 5-8,	
		1999),141-143	
		MA, Y., et al., "Zirconium Oxide Based Gate Dielectrics with equivalents Oxide	
		Thickness of LEss Than 1.0 nm and Performance of Submicron MOSFET using a	ļ ·
		Nitride Gate Replacement Process", IEDM - Technical Digest, (1999),pp. 149-152	
		MARSHALEK, R., et al., "Photoresponse Characteristics of Thin-Film Nickel-	
		Nickel Oxide-Nickel Tunneling Junctions", IEEE Journal of Quantum Electronics,	1
		QE-19(4), (1983),pp. 743-754	
	i	MASUOKA, F., et al., "A 256K Flash EEPROM using Triple Polysilicon	
1 1		Technology", IEEE International Solid-State Circuits Conference, Digest of	
1		Technical Papers, (1985),168-169	
		MASUOKA, F., et al., "A New Flash EEPROM Cell using Triple Polysilicon	
l i		Technology", International Electron Devices Meeting, Technical Digest, San	1
		Francisco, CA,(1984),464-467	<u> </u>
		MORI, S., et al., "Reliable CVD Inter-Poly Dielectrics for Advanced E&EEPROM",	
		Symposium on VSLI Technology, Digest of Technical Papers, (1985),16-17	
		MULLER, H., "Electrical and Optical Properties of Sputtered In2O3 Films",	
		Physica Status Solidi, 27(2), (1968),pp.723-731	1
		PARANJPE, AJIT, et al., "Atomic layer deposition of AlOx for thin film head gap	
		applications", Journal of the Electrochemical Society, (September 2001),pp. 465-	
<u> </u>		471	
1		PASHLEY, R., et al., "Flash Memories: the best of two worlds", IEEE Spectrum,	
		26(12), (December 1989),30-33	
		POLLACK, S., et al., "Tunneling Through Gaseous Oxidized Films of Al2O3",	
<u></u>		Transactions of the Metallurgical Society of AIME, 233, (1965),497-501	

1	Transactions of the	ic metaliargical cociet	7.01 MINE, 200, (1000),701 001	
		0/		
EXAMINER	ah am/ran)	M	DATE CONSIDERED C	6/28/05
$\overline{}$	//			7 7

PTO/S9/064 10-01 Approved for use through 19/31/2002, OMB 651-0031 US Patent & Trademath Office U.S. DEPARTMENT OF COMMERCE on of information unless is ordinals a unit CH4P month or main.

Substitute for form 1449A/PTO	Complete If Known	/
INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	Unknown 10/784, 038
(Use as many sheets as necessary)	Filing Date	Even Date Herewith -02-27-04
	First Named Inventor	Forbes, Leonard
	Group Art Unit	-Unknown 2827
	Examiner Name	Pham, Ly
Sheet 5 of 5	Attorney Docket No: 1	1303.024US2

	ОТН	ER DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner initials*	Cite No 1	include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T*
id		QI, W , "MOSCAP and MOSFET characteristics using ZrO2 gate dielectric deposited directly on Si", IEDM - Technical Digest, (1999),145-148	
		ROBERTSON, J., "Band offsets of wide-band-gap oxides and implications for future electronic devices", <u>Journal of Vacuum Science & Technology B</u> (Microelectronics and Nanometer Structures), 18(3), (May-June 2000),1785-1791	
		ROBERTSON, J., "Schottky barrier heights of tantalum oxide, barium strontium-titanate, lead titanate, and strontium bismuth tantalate", <u>Applied Physics Letters</u> , 74(8), (1999),pp. 1168-1170	
		SHI, Y., "Tunneling Leakage Current in Ultrathin (<4 nm) Nitride/Oxide Stack Dielectrics", IEEE Electron Device Letters, 19(10), (Oct. 1998),pp. 388-390	
		SIMMONS, J., "Generalized Formula for the Electric Tunnel Effect between Similiar Electrodes Separated by a Thin Insulating Film", <u>Journal of Applied Physics</u> , 34(6), (1963),1793-1803	
		SMITH, RYAN C., et al., "Chemical vapour deposition of the oxides of titanium, zirconium and hafnium for use as high-k materials in microelectronic devices. A carbon-free precursor for the synthesis if hafnium dioxide", Advanced Materials for Optics and Electronics, (2000),pp. 105-106	
		SWALIN, R., "Equilibrium between Phases of Variable Composition", Thermodynamics of Solids, 2nd Edition, (1972),pp. 165-180	
		SZE, S., "Physics of Semiconductor Devices, Second Edition", <u>John Wiley & Sons, New York</u> , (1981),553-556	
		YAN, J., et al., "Structural and electrical characterization of TiO2 grown from titanium tetrakis-isopropoxide (TTIP) and TTIP/H2O ambients", <u>Journal Vac. Sci. Technol. B</u> , 14(3), (1996),pp. 1706-1711	
V		ZHANG, H., et al., "Atomic Layer Deposition of High Dielectric Constant Nanolaminates", Journal of The Electrochemical Society, 148(4),(2001),F63-F66	

EXAMINER PRAMISM MI DATE CONSIDERED 06/28/05

PTO/SB/08A(10-01)
Approved for use through 10/31/2002, OMB 651-0031
Petent & Tradement Office; U.S. DEPARTMENT OF CONSUMERCE

Substitute for form 1449A/PTO
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT
USe as many sheets as necessary)

The statement and the statement of the statement

US PATENT DOCUMENTS						
Examiner initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate
	US-6,169,306	01/02/2001	Gardner, Mark I., et al.	257	310	07/27/1998

		FOREIGN PATENT	DOCUMENTS	****		
Examiner Initials*	Foreign Document No	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	T²

	OTHER	R DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s),	T
Minara	1 10	publisher, city and/or country where published.	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line (trough citation if not in conformance and not considered, Include copy of this form with next communication to applicant, Applicant's unique citation designation number (optional) 2 Applicant is to prace a check mark here if English language Translation is attached

PTO/SB/084 (10-01
Approved for use through 10/31/2002, OMB 651-0031
Patent & Tradinisht Office: U.S. DEPARTMENT OF COMMERCE

nder the Papareont Reduction Act of 1995, no persons are required to respond to a co Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE **Application Number** 10/789,038 STATEMENT BY APPLICANT February 27, 2004 Filing Date Forbes, Leonard **First Named Inventor** 281T **Group Art Unit Examiner Name** Pham, Ly Attorney Docket No: 1303.024US2

US PATENT DOCUMENTS						
Examiner Initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate
11	US-4,688,078	08/18/1987	Hseih, Ning	257	321	12/11/1985
1	US-4,939,559	07/03/1990	DiMaria, D. J., et al.	257	38	04/01/1986
	US-5,488,612	01/30/1996	Heybruck, W. F.	714	725	10/04/1993
	US-5,959,465	09/28/1999	Beat, R.	326	39	12/29/1995
	US-6,377,070	04/23/2002	Forbes, Leonard	326	41	02/09/2001
	US-6,514,842	02/04/2003	Prall, K. D., et al.	438	593	08/08/2001
V	US-6,730,575	05/04/2004	Eldridge, Jerome M.	257	310	08/30/2001

	FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Foreign Document No	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	1,5

	OTHER	R DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No 1	include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²

EXAMINER PROMISE DATE CONSIDERED 06/28/05

Substitute for form 1449A/PTO	Complete d Known	returned (a response to a conference of information unfertil a conference to 4 0 1/3 control extends
INFORMATION DISCLOSURE	Application Number	10/789,038
STATEMENT BY APPLICATED	Filing Date	February 27, 2004
	First Named Inventor	Forbes, Leonard
DEC 2 0 2004 20	Group Art Unit	2811 2827
- 1	Examiner Name	Pham, Ly
Sheet 1 of 1	Attorney Docket No: 1	303.024US2

US PATENT DOCUMENTS				
Examiner Initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Filing Date If Appropriate
B	US-5,474,947	12/12/1995	Chang, K., et al.	12/27/1993
1	US-6,009,011	12/28/1999	Yamauchi, Y.	12/24/1997
	US-6,317,364	11/13/2001	Guterman, D. C., et al.	10/13/2000
	US-6,341,084	01/22/2002	Numata, H., et al.	05/15/2001
Q.	US-6,754,108	06/22/2004	Forbes, L.	08/30/2001

•	······································	FOREIGN PATENT	DOCUMENTS	
Examiner Initials*	Foreign Document No	Publication Date	Name of Patentee or Applicant of cited Document	T²

	OTHER	R DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner	Cite	include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item	1,
Initials*	No 1	(book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s),	
i		publisher, city and/or country where published.	

EXAMINER

DATE CONSIDERED

PTO/SB/08A(10-01) Approved for use through 19/31/2002, Os/8 651-0031

Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE 10/789,038 **Application Number** STATEMENT BY APPLICANT (Use as many sheets as necessary) February 27, 2004 **Filing Date** Forbes, Leonard **First Named Inventor Group Art Unit** 2827 <u>AU6</u> 0 5 2005 **Examiner Name** Pham, Ly Attorney Docket No: 1303.024US2 Sheet 1 of 1

US PATENT DOCUMENTS						
Examiner Initial	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Filing Date If Appropriate		
И	US-2002/0008324-A1	01/24/2002	Shinkawata, H	01/23/2001		
	US-2003/0043637-A1	03/06/2003	Forbes, Leonard, et al.	08/30/2001		
	US-2003/0207032-A1	11/06/2003	Ahn, Kie Y., et al.	05/02/2002		
	US-2003/0207540-A1	11/06/2003	Ahn, Kie Y., et al.	05/02/2002		
	US-2005/0023595-A1	02/03/2005	Forbes, L., et al.	08/31/2004		
	US-2005/0023603-A1	02/03/2005	Eldridge, J. M., et al.	08/30/2004		
	US-5,618,761	04/08/1997	Eguchi, K., et al.	09/11/1995		
	US-5,619,051	04/08/1997	Endo, N.	06/23/1995		
	US-6,740,928	05/25/2004	Yoshii, S., et al.	01/24/2003		
V	US-6,778,441	08/17/2004	Forbes, L., et al.	08/30/2001		

·	FOREIGN PATEN	T DOCUMENTS	
Examiner Foreign Document No Initials*	Publication Date	Name of Patentee or Applicant of cited Document	T²

OTHER DOCUMENTS - NON PATENT LITERATURE DOCUMENTS			
Examiner Cite	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s),	T²	
<u> </u>	publisher, city and/or country where published.		

EXAMINER SHAMM MM DATE CONSIDERED OAT

STRE WO

PTO/SB/GB/(10-01)
Approved for use through 10/31/2002, OM9 651-0031
Patient & Trademark Office: U.S. DEPARTMENT OF COMMERCE

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Complete if Known					
Application Number	10/789,038				
Filing Date	February 27, 2004				
First Named Inventor	Forbes, Leonard				
Group Art Unit	2827				
Examiner Name	Pham, Ly				

Sheet 1 of 1

Attorney Docket No: 1303.024US2

US PATENT DOCUMENTS					
Examiner Initial	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Filing Date If Appropriate	
H	US-2005/0169054A1	08/04/2005	Forbes, L.	02/22/2005	

Examiner Foreign Documentalis*	ment No	Publication Date	Name of Patentee or Applicant of cited Document	T 2

	OTHE	R DOCUMENTS - NON PATENT LITERATURE DOCUMENTS	
	Examiner Cite	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item	Tr
1	Initials* No.1	(book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s),	1 [
1		publisher, city and/or country where published.	1 1

EXAMINER

DATE CONSIDERED

09/23/2005